

Electronic Patent Application Fee Transmittal

| | | | | |
|---|---|-----------------|---------------|-----------------------------|
| Application Number: | 10802150 | | | |
| Filing Date: | 17-Mar-2004 | | | |
| Title of Invention: | Etching process including plasma pretreatment for generating fluorine-free carbon-containing polymer on a photoresist pattern | | | |
| First Named Inventor/Applicant Name: | Keun-Hee Bai | | | |
| Filer: | Frank Chau/Jaewoo Park | | | |
| Attorney Docket Number: | 8021-215 (SS-19582-US) | | | |
| Filed as Large Entity | | | | |
| Utility Filing Fees | | | | |
| Description | Fee Code | Quantity | Amount | Sub-Total in USD(\$) |
| Basic Filing: | | | | |
| Pages: | | | | |
| Claims: | | | | |
| Miscellaneous-Filing: | | | | |
| Petition: | | | | |
| Patent-Appeals-and-Interference: | | | | |
| Notice of appeal | 1401 | 1 | 510 | 510 |
| Post-Allowance-and-Post-Issuance: | | | | |
| Extension-of-Time: | | | | |

| Description | Fee Code | Quantity | Amount | Sub-Total in USD(\$) |
|-----------------------------------|----------|----------|--------|----------------------|
| Extension - 1 month with \$0 paid | 1251 | 1 | 120 | 120 |
| Miscellaneous: | | | | |
| Total in USD (\$) | | | | 630 |